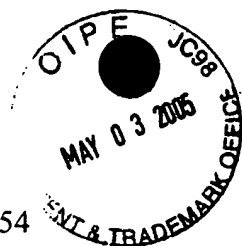


00684.003654

PATENT APPLICATION

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:	)	
Takako YAMAGUCHI et al.	)	Examiner: Unassigned
Application No.: 10/529,891	)	Group Art Unit: Unassigned
	)	
Entry into U.S. National	)	
Stage Under 35 U.S.C. § 371: April 1, 2005	)	
	)	
For: EXPOSURE MASK, METHOD OF	)	May 3, 2005
DESIGNING AND MANUFACTURING	)	
THE SAME, EXPOSURE METHOD AND	)	
APPARATUS, PATTERN FORMING	)	
METHOD, AND DEVICE	)	
MANUFACTURING METHOD	)	

**Mail Stop Amendment**  
 Commissioner for Patents  
 P.O. Box 1450  
 Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Sir:

In compliance with the duty of disclosure under 37 C.F.R. § 1.56 and in accordance with the practice under 37 C.F.R. §§ 1.97 and 1.98, the Examiner's attention is directed to the documents listed on the enclosed PTO-1449 form. Copies of the Japanese patent documents (with English language abstracts) and PCT publication are also enclosed.

U.S. Patent No. 6,171,730 is discussed on pages 2-3 of the specification.

Japanese patent document number 11-317345 and U.S. Patent No. 6,497,996 are discussed on page 3 of the subject specification. U.S. Patent No. 6,671,034 and U.S. Patent Application Publication No. 2004/0090610 A1 are English language counterparts of the '345 Japanese patent document.

U.S. Patent No. 6,171,730 B1, U.S. Patent Application Publication No. 2001/046719 A1, International Application No. WO 03/001869 A, McNab et al. "Analytic

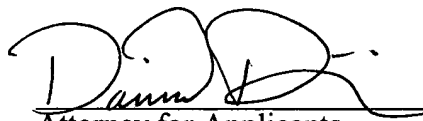
study of gratings patterned by evanescent near field optical lithography,” Luo et al.  
“Surface plasmon resonant interference nanolithography technique,” and Alkaisi et al.  
“Nanolithography in the Evanescent Near Field” were cited in an International Search  
Report, which was mailed on September 27, 2004, from the European Patent Office in  
corresponding International Application No. PCT/JP2004/009375. Copies of the  
International Search Report and a Written Opinion mailed September 27, 2004 are also  
enclosed.

Applicants request that the above information be considered by the Examiner and  
that a copy of the enclosed PTO-1449 form be initialed and returned indicating that such  
information has been considered.

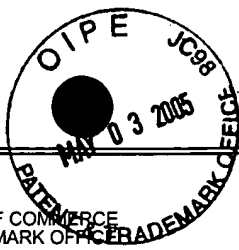
This Information Disclosure Statement is being filed before the issuance of a first  
Office Action on the merits. Therefore, no fee under 37 C.F.R. 1.97(c)(2) is believed due.  
Nevertheless, the Commissioner may charge Deposit Account No. 06-1205, should any fee  
be due for filing this paper.

Applicants’ undersigned attorney may be reached in our Washington D.C. office  
by telephone at (202) 530-1010. All correspondence should continue to be directed to our  
address given below.

Respectfully submitted,

  
\_\_\_\_\_  
Attorney for Applicants  
David A. Divine  
Registration No. 51,275

FITZPATRICK, CELLA, HARPER & SCINTO  
30 Rockefeller Plaza  
New York, New York 10112-3800  
Facsimile: (212) 218-2200



FORM PTO 1449 (modified)		ATTY DOCKET NO. 00684.003654		APPLICATION NO. 10/529,891	
U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		APPLICANT Takako YAMAGUCHI et al.			
LIST OF REFERENCES CITED BY APPLICANT(S) (Use several sheets if necessary)		FILING DATE April 1, 2005		GROUP Unassigned	
May 3, 2005					
U.S. PATENT DOCUMENTS					
*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS SUBCLASS FILING DATE IF APPROPRIATE
		US 6,171,730 B1	01/09/2001	Kuroda et al.	430 5
		2001/0046719 A1	11/29/2001	Yamaguchi et al.	438 11
		2003/0129545 A1	07/10/2003	Kik et al.	430 313
		US 6,497,996	12/24/2002	Naya et al.	430 323
		US 6,671,034 B1	12/30/2003	Hatakeyama et al.	355 67
		2004/0090610 A1	05/13/2004	Hatakeyama et al.	355 67
FOREIGN PATENT DOCUMENTS					
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS SUBCLASS TRANSLATION YES/NO/ OR ABSTRACT
		11-317345	11/16/1999	Japan	Abstract
		WO 03/001869 A2	01/09/2003	PCT	
OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)					
		International Search Report mailed September 27, 2004, issued in corresponding International Application No. PCT/JP2004/09375.			
		Written Opinion mailed September 27, 2004, issued in International Application No. PCT/JP2004/09375.			
		McNab, S. J., et al., "Analytic study of gratings patterned by evanescent near field optical lithography," J. Vac. Sci. Technol. B 18(6), Nov/Dec 2000, pp. 2900-2904.			
		Luo, Xiangang, et al., "Surface plasmon resonant interference nanolithography technique," Applied Physics Letters, Vol. 84, No. 23, June 7, 2004, pp. 4780-4782.			
		Alkaisi, Maan M., et al., "Nanolithography in the Evanescent Near Field," Advanced Materials, 13, No. 12-13, July 4, 2001, pp. 877-887.			
EXAMINER			DATE CONSIDERED		

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.